

10763175_CLS

Most Frequently Occurring Classifications of Patents Returned
From A Search of 10763175 on May 27, 2004

Original Classifications

15 250/492.22
7 250/492.2
5 355/53
4 430/5
3 250/398
2 430/22

Cross-Reference Classifications

13 250/398
6 250/492.2
5 250/492.22
5 250/492.23
5 430/296
4 250/396R
4 430/942
3 250/492.3
3 313/470
3 355/67
3 430/30
2 313/403
2 355/77
2 430/323
2 430/328
2 430/394
2 430/396
2 430/494
2 445/47

Combined Classifications

20 250/492.22
16 250/398
13 250/492.2
6 250/492.23
5 355/53
5 430/296
5 430/5
4 250/396R
4 430/30
4 430/942
3 250/492.3
3 313/470
3 355/67
3 430/22

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3 430/394
3 430/396
2 313/403
2 355/77
2 430/23
2 430/24
2 430/26
2 430/323
2 430/328
2 430/494
2 445/47

10763175_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

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20 250/492.22 (15 OR, 5 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.22 ..Pattern control

16 250/398 (3 OR, 13 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/398 .With target means

13 250/492.2 (7 OR, 6 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices

6 250/492.23 (1 OR, 5 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.23 ..Variable beam

5 355/53 (5 OR, 0 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/53 .Step and repeat

5 430/296 (0 OR, 5 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING
NONPLANAR OR
R PRODUCT
430/296 .Electron beam imaging

5 430/5 (4 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
MAKING

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430/5 .Radiation mask

4 250/396R (0 OR, 4 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING

4 430/30 (1 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST
OR MEASUREMENT

4 430/942 (0 OR, 4 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/942 ELECTRON BEAM

3 250/492.3 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation

3 313/470 (0 OR, 3 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/364 CATHODE RAY TUBE
313/461 .Screen
313/470 ..Mosaic

3 355/67 (0 OR, 3 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/67 .Illumination systems or details

3 430/22 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/22 .REGISTRATION OR LAYOUT PROCESS OTHER THAN COLOR
R PROOFING

3 430/394 (1 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/394 PLURAL EXPOSURE STEPS

3 430/396 (1 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,

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COMPOSITION, OR PRODUCT THEREOF
EFFECTING FRONTAL RADIATION MODIFICATION DURING

430/396

G

EXPOSURE, E.G., SCREENING, MASKING, STENCIL
ING, ETC.

2 313/403 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/364 CATHODE RAY TUBE
313/402 .Shadow mask, support or shield
313/403 ..Non-circular aperture

2 355/77 (0 OR, 2 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/77 .Methods

2 430/23 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/23 PRODUCING CATHODE-RAY TUBE OR ELEMENT THEREOF

2 430/24 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/23 PRODUCING CATHODE-RAY TUBE OR ELEMENT THEREOF

430/24 .Using specific control or specific
modification of exposure, i.e., by manipula
tion of
radiation source or exposure through elemen
ts other than
shadow mask

2 430/26 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/23 PRODUCING CATHODE-RAY TUBE OR ELEMENT THEREOF

430/26 .With faceplate of phosphoric stripes

2 430/323 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCIN

G NONPLANAR OR

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PRINTING SURFACE - PROCESS, COMPOSITION,

OR PRODUCT

430/322 . Forming nonplanar surface
430/323 .. Including etching substrate

2 430/328 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR

PRINTING SURFACE - PROCESS, COMPOSITION, O

R PRODUCT

430/328 . Post imaging radiant energy exposure

2 430/494 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/494 INCLUDING EXPOSURE STEP OR SPECIFIED
PRE-EXPOSURE STEP PERFECTING EXPOSURE

2 445/47 (0 OR, 2 XR)
Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR
DEVICE MANUFACTURING
445/1 PROCESS
445/46 .Electrode making
445/47 ..Multi-apertured panel making, e.g., CRT mask